Errata: Analysis of characteristic parameters of a plasma ion source and of ion-assisted deposited optical thin films

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This article [Opt. Eng. 44, 103601 (2005)] was originally published on 4 October 2005 with three references missing from the reference list. These three references should be included in the reference list:


These additional references and the necessary callouts should have been located within the paper as detailed below.

Reference 19 should appear on p. 2, after the seventh sentence of Sec. 2.1 as follows:

Ion energy measurements were made using a versatile multigrid retarding-field ion energy analyzer (IEA) for the determination of ion energy distribution functions (IEDFs) in vacuum processing systems.19

Reference 20 should appear on p. 2, after the eighth sentence of Sec. 2.1 as follows:

This study was published previously20 and discussed briefly here.

Reference 21 should be called out on p. 7, before the first sentence of the last paragraph of Sec. 4, and on p. 8, after the third and last sentences of the first paragraph of Sec. 5, and after the captions of Figs. 16 and 17, respectively, as follows:

The previous work on moisture stable stacks was achieved by D.E. Morton.21

Fig. 16 Twelve-layer TiO2/SiO2(HL)6 stack showing overlapping wet and dry scans.21

Fig. 17 Drive voltage versus drive current for various pumping speeds at the initial pressures of $2 \times 10^{-4}$ and $3 \times 10^{-4}$ Torr.21

This was studied previously by D.E. Morton. Complete details of the study are contained in Ref. 21.